Method to pattern etch masks in two inclined planes for three-dimensional nano- and microfabrication
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Published in:
Journal of Vacuum Science and Technology, B: Microelectronics and Nanometer Structures--Processing, Measurement, and Phenomena

DOI:
10.1116/1.3683157

Published: 01/01/2012

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Citation: J. Vac. Sci. Technol. B 30, 023401 (2012); doi: 10.1116/1.3683157
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(Received 3 January 2012; accepted 5 January 2012; published 15 February 2012)

[DOI: 10.1116/1.3683157]

In this article the author list is displayed in incorrect order. The correct order is R. Willem Tjerkstra, Léon A. Woldering, Johanna M. van den Broek, Fred Roozeboom, Irwan D. Setija, and Willem L. Vos.

This is already corrected in the online version of the article.